

Supporting Information

Dipole-correlated carrier transportation and orbital reconfiguration in strain-distorted $\text{SrNb}_x\text{Ti}_{1-x}\text{O}_3$

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Additional XRD and RSM results

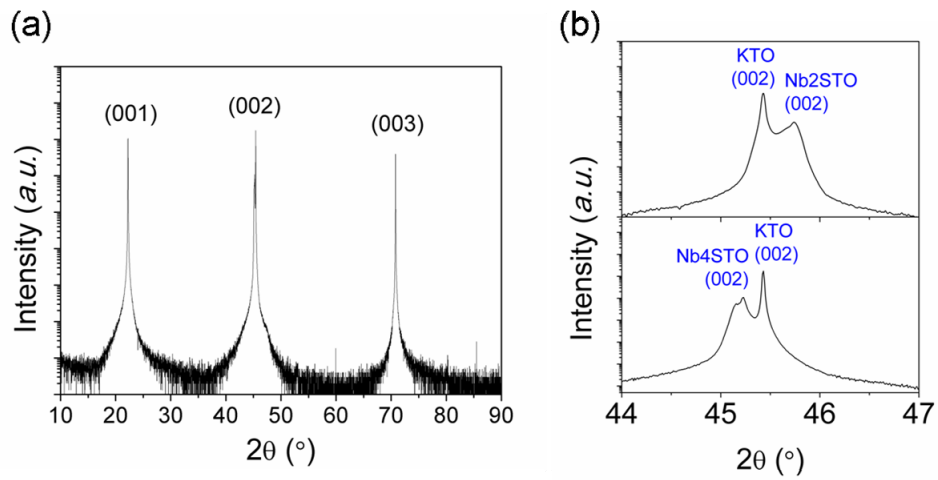


Figure S1. (a) XRD patterns (θ - 2θ scan) for $\text{SrNb}_{0.4}\text{Ti}_{0.8}\text{O}_3/\text{KTaO}_3$ (001) and (b) XRD patterns $\text{SrNb}_{0.2}\text{Ti}_{0.8}\text{O}_3/\text{KTaO}_3$ (001) and $\text{SrNb}_{0.4}\text{Ti}_{0.6}\text{O}_3/\text{KTaO}_3$ (001). The film and substrate show the same crystal structure and orientation, since the diffraction peaks for the film are present beside those for the substrate. It indicates that as-grown thin films exhibit the same crystal structure and orientation as compared to the substrate.

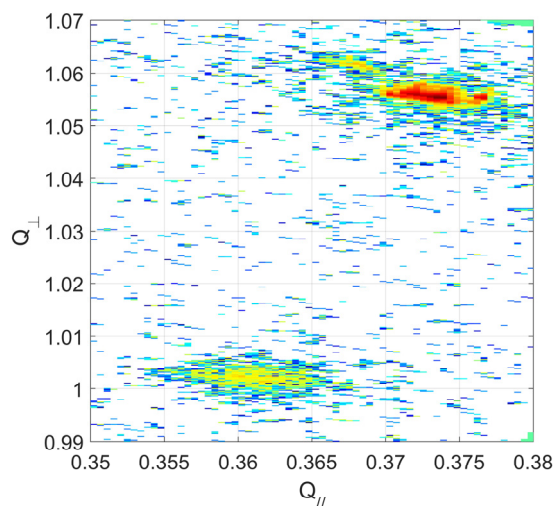


Figure S2. RSM results for *as-grown* SrNb_{0.2}Ti_{0.8}O₃/LaAlO₃ (001) with a thickness around 50 nm. The upper and lower diffraction patterns are the reciprocal space vectors of [114] from the substrate and film, respectively. Smaller $Q_{//}$ and Q_{\perp} for the film compared with the substrate were observed. The interfacial strain is completely relaxed at an early stage of the deposition from a large lattice mismatch (3.65%).

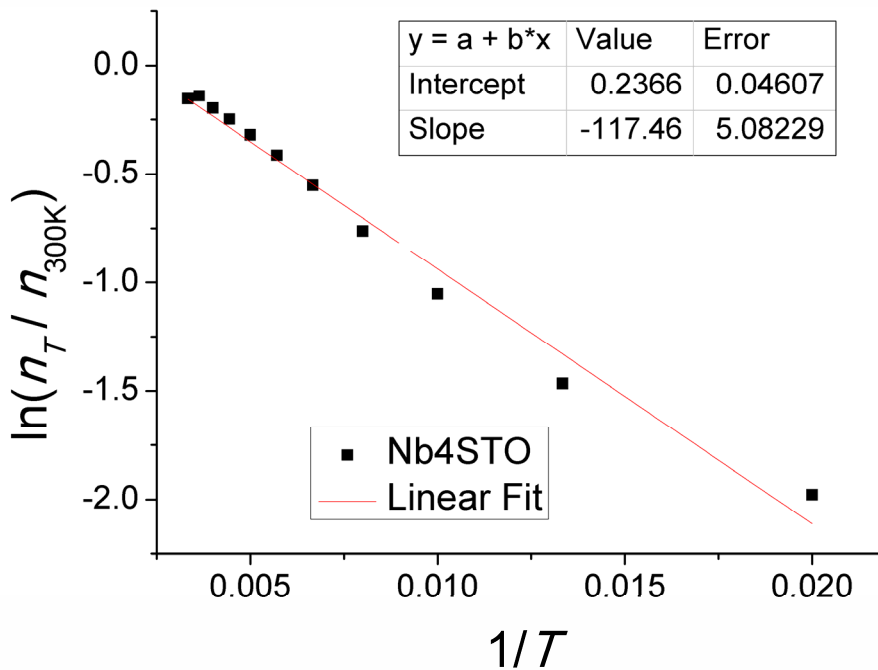
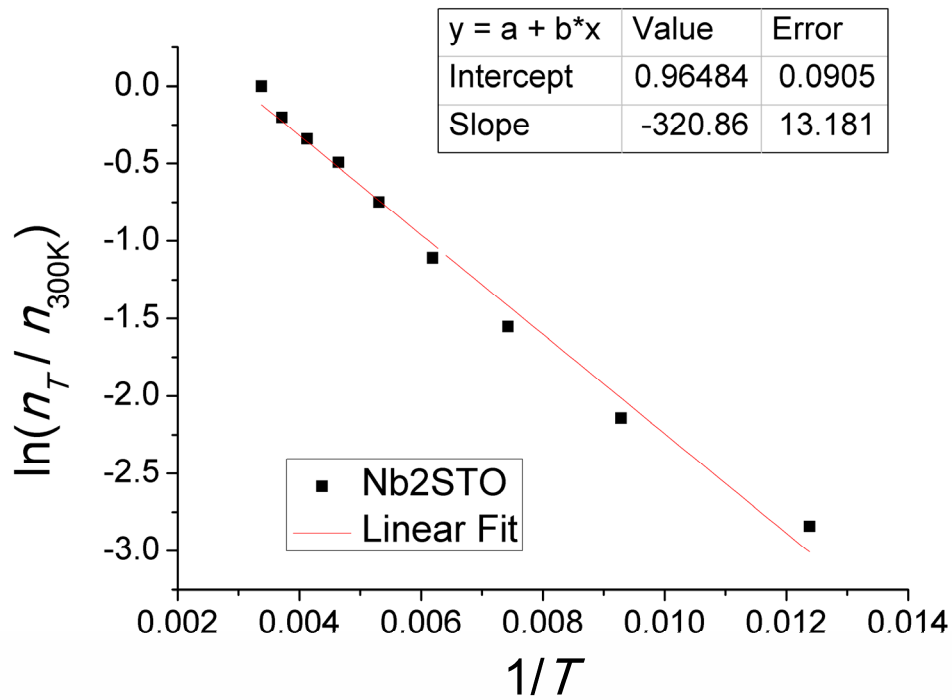


Figure S3. Estimation of the activation energy was estimated from the temperature dependence of carrier concentration as shown in Figure 2b. The temperature dependence of the carrier concentration by, $n = N_{sat} \cdot \text{Exp}\left(\frac{-\Delta E}{k_B T}\right)$, from 50-300 K. Transforming the above

formula to $\ln(n / n_{300K}) = \ln(N_{sat.} / n_{300K}) + \left(\frac{-\Delta E}{k_B}\right)(1 / T)$ and plotting $\ln(n / n_{300K})$ vs. $1 / T$,

obtains the above two graph for Nb2STO/KTO and Nb4STOKTO, respectively. The slope indicates the activation energy divided by the Boltzmann constant.